CLAIMS

1. A transparent conductive laminate comprising a transparent polymer substrate, an uneven cured resin layer-1 formed on at least one side of the substrate and a transparent conductive layer formed on the cured resin layer-1 directly or through another layer, wherein

(A) the cured resin layer-1 comprises (i) a cured resin component, (ii) at least one type of fine particles A having an average primary particle diameter of 0.5 to 5 μm and (iii) super fine particles C having an average primary particle diameter of 100 nm or less made of at least one selected from the group consisting of a metal oxide and a metal fluoride;

(B) the content of the fine particles A in the cured resin layer-1 is 0.3 part or more by weight and less than 1.0 part by weight based on 100 parts by weight of the cured resin component (i);

(C) the content of the super fine particles C in the cured resin layer-1 is 1 to 20 parts by weight based on 100 parts by weight of the cured resin component (i);

(D) the thickness of the cured resin layer-1 is 0.5 to 5 μm; and

(E) the haze value defined by JIS K7136 based on the transparent polymer substrate and the cured resin layer-1 is 1 % or more and less than 8 %.

2. The transparent conductive laminate according to claim 1, wherein the cured resin layer-1 does not contain a thermoplastic resin.

3. The transparent conductive laminate according to claim 1, wherein the super fine particles C comprise at least one selected from the group consisting of $Al_2O_3$, $Bi_2O_3$, $CeO_2$, $In_2O_3$, ($In_2O_3 \cdot SnO_2$), $HfO_2$, $La_2O_3$, $MgF_2$, $Sb_2O_5$, ($Sb_2O_5 \cdot SnO_2$), $SiO_2$, $SnO_2$, $TiO_2$, $Y_2O_3$, ZnO and $ZrO_2$.

4. The transparent conductive laminate according to claim 1, wherein the arithmetic average roughness (Ra) defined by JIS B0601-1994 of the cured resin layer-1 is 50 nm or more and less than 500 nm and the 10-point average roughness (Rz) defined by JIS B-0601-1982 of the cured resin layer-1 is 100 nm or more and less than 1,000 nm.

5. The transparent conductive laminate according to claim 1, which further has a cured resin layer-2 having a refractive index of 1.20 to 1.55 and a thickness of 0.05 to 0.5 μm between the cured resin layer-1 and the transparent conductive layer.

6. The transparent conductive laminate according to claim 1, which further has an optical interference layer consisting of at least one low-refractive index layer and at least one high-refractive index layer between the cured resin layer-1 and the transparent conductive layer, the low-refractive index layer being in contact with the transparent conductive layer.

7. The transparent conductive laminate according to claim 1, wherein the transparent conductive layer is a crystalline layer comprising indium oxide as the main component and has a thickness of 5 to 50 nm.

8. The transparent conductive laminate according to claim 1, wherein a cured resin layer-3 having an anti-glare function is formed on the surface of the transparent polymer substrate opposite to the transparent conductive layer.

9. The transparent conductive laminate according to claim 8, wherein the haze value defined by JIS K7136 based on the transparent polymer substrate, cured resin layer-1 and cured

resin layer-3 is 4 % or more and less than 18 %.

10. A transparent touch panel comprising two transparent electrode substrates having a transparent conductive layer on at least one side, which are arranged such that the transparent conductive layers are opposed to each other, wherein

at least one of the transparent electrode substrates is the transparent conductive laminate of claim 1.

11. A transparent touch panel comprising two transparent electrode substrates having a transparent conductive layer on at least one side, which are arranged such that the transparent conductive layers are opposed to each other, wherein

at least one of the transparent electrode substrates is the transparent conductive laminate of claim 8.